#### **ECE 340: Semiconductor Electronics**

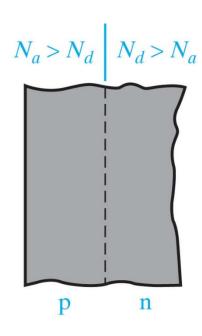
**Chapter 5: Junction (part I)** 

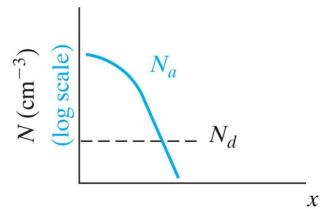
Wenjuan Zhu

### **Outline**

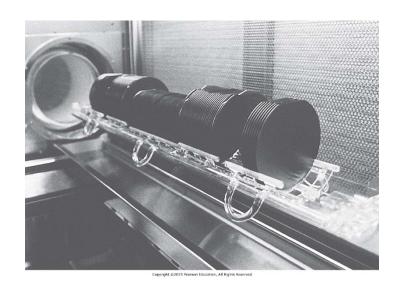
- Fabrication of p-n Junctions
- Equilibrium Condition
  - The Contact Potential
  - Equilibrium Fermi Levels
  - Space Charge at a Junction

## Form pn junction by thermal diffusion

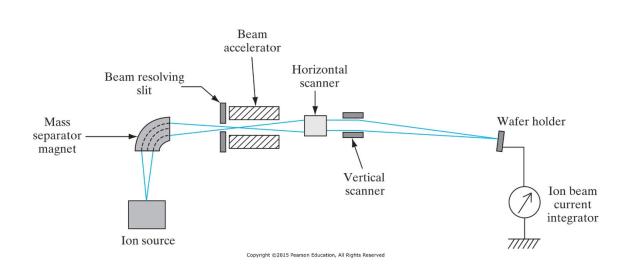


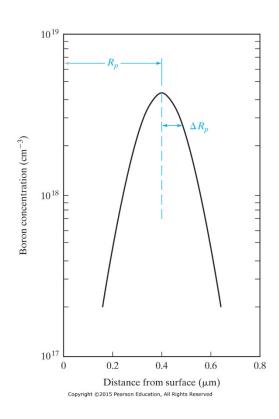






## Ion implantation



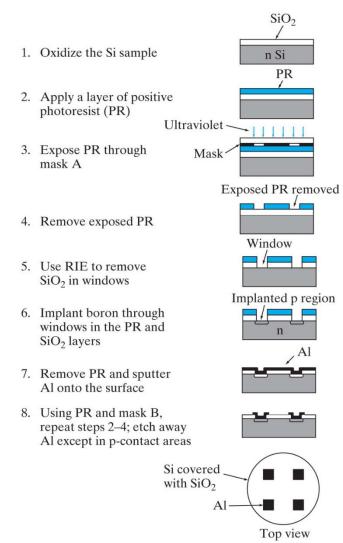


## Process flow for pn junction formation





Mask B (metallization)

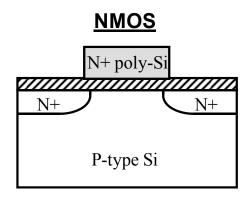


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## Why do we study pn junction?

PN junction is the basic building block for:

- Transistors: computing and memory
- LEDs (light emitting diode), convert electricity to light
- Lasers: convert electricity to light
- Solar cells: convert sunlight to current
- Photodetectors: detect light
- Rectifiers: convert AC to DC current





### **Outline**

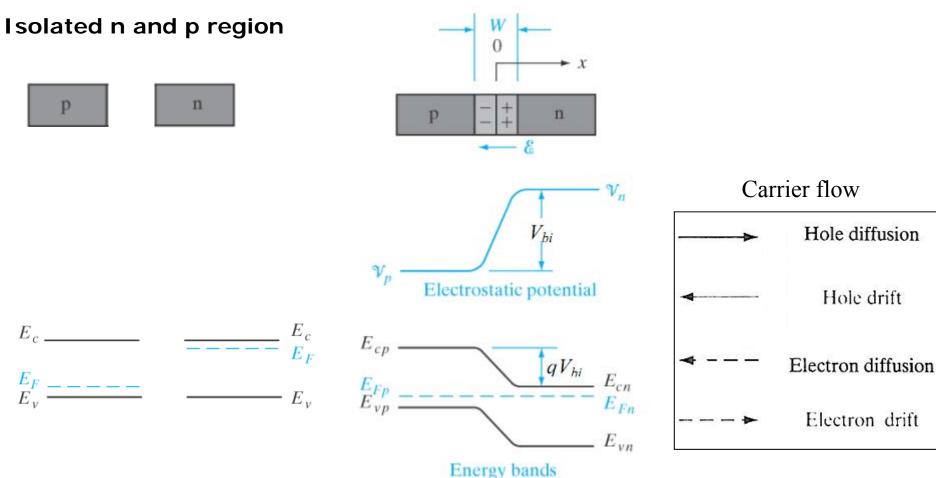
Fabrication of p-n Junctions



- Equilibrium Condition
  - The Contact Potential
  - Equilibrium Fermi Levels
  - Space Charge at a Junction

# Form PN junction

#### pn junction at equilibrium



Carrier diffusion → leave behind uncompensated donor (acceptor) ions → resulting electric field → drift current balances the diffusion current at equilibrium.

### At equilibrium

No net electron or hole current:

$$J_p(drift) + J_p(diff.) = 0$$
  
 $J_n(drift) + J_n(diff.) = 0$ 

- The electric field builds up to the point where the net current is zero at equilibrium.
- The region W with left-behind uncompensated donor (acceptor) ions called transition region.
- The potential difference  $V_0$  across W called contact potential

$$V_0 = V_n - V_p$$

### Built-in electric field

### At equilibrium:

$$J_p(x) = q\mu_p p(x)\mathcal{E}(x) - qD_p \frac{dp(x)}{dx} = 0$$

Use Einstein relation  $\frac{D}{U} = \frac{1}{U}$ 

$$\Longrightarrow \quad \varepsilon = \frac{kT}{q} \frac{1}{p} \frac{dp}{dx}$$

Since 
$$\varepsilon = -\frac{dV(x)}{dx}$$

## Contact potential

$$\Rightarrow V_n - V_p = -\frac{kT}{q} (lnP_p - lnP_p)$$

$$\Rightarrow V_0 = \frac{kT}{q} ln \left( \frac{P_p}{P_n} \right) \qquad \text{Contact potential}$$

Or 
$$V_0 = \frac{kT}{q} ln \left( \frac{N_a}{n_i^2/N_d} \right) = \frac{kT}{q} ln \left( \frac{N_a N_d}{n_i^2} \right)$$

### Carrier concentration ratio

 The hole concentration ratio between p side and n side at the edge of transition region:

$$\frac{P_p}{P_n} = e^{qV_0/kT}$$

Since 
$$P_p n_p = n_i^2 = P_n n_n$$

### **Outline**

- Fabrication of p-n Junctions
- Equilibrium Condition
  - The Contact Potential



- Equilibrium Fermi Levels
- Space Charge at a Junction

### Equilibrium Fermi levels

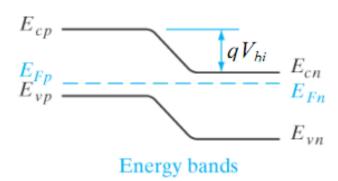
• At equilibrium, Fermi level on either sides are equal  $(E_{Fp}=E_{Fn})$ , combine with

$$\frac{P_p}{P_n} = e^{qV_0/kT} = \frac{N_v e^{-(E_{Fp} - E_{vp})/kT}}{N_v e^{-(E_{Fn} - E_{vn})/kT}}$$

$$\Rightarrow qV_0 = E_{vp} - E_{vn}$$

 $V_p$  Electrostatic potential

the contact potential times q is equal to the energy difference between n and p region



### **Outline**

- Fabrication of p-n Junctions
- Equilibrium Condition
  - The Contact Potential
  - Equilibrium Fermi Levels



Space Charge at a Junction

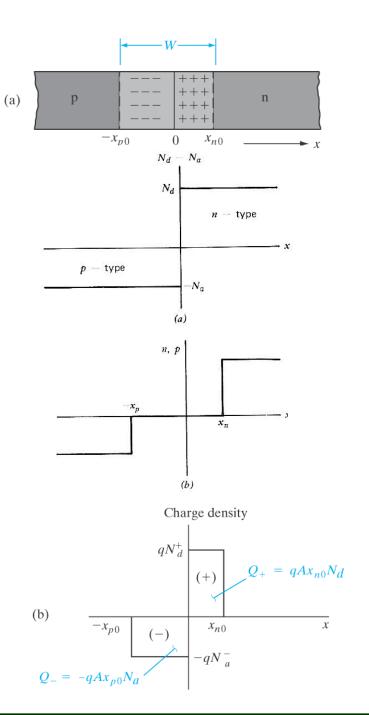
## Space charge at a junction

- Depletion approximation: assumption of carrier depletion within W and neutrality outside W.
- Penetration of the space charge region:

$$Q_{+} = Q_{-}$$

$$qAx_{p0}N_{a} = qAx_{n0}N_{d}$$

$$x_{p0}N_a = x_{n0}N_d$$



### Electric field

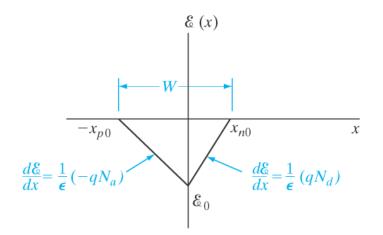
Poisson's equation:

$$\frac{d\mathcal{E}(x)}{dx} = \frac{q}{\epsilon}(p - n + N_d^+ - N_a^-)$$

 If neglect the contributions of carriers in space charge, and assume complete ionization of impurities:

$$\frac{d\mathcal{E}(x)}{dx} = \frac{q}{\epsilon} N_d \qquad 0 < x < x_{n0}$$

$$\frac{d\mathcal{E}(x)}{dx} = -\frac{q}{\epsilon} N_a \qquad -x_{p0} < x < 0$$



### Built-in electric field

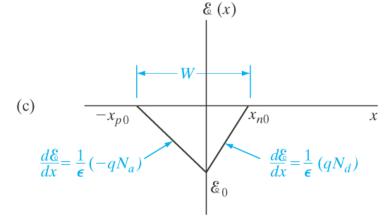
#### Built-in field:

$$\mathcal{E}(x) = -\frac{qN_d}{\epsilon}(x_{n0} - x) \quad 0 < x < x_{n0}$$

$$\mathcal{E}(x) = -\frac{qN_a}{\epsilon}(x_{p0} + x) \quad -x_{p0} < x < 0$$

 The maximum electric field located at the interface of n and p junction (x=0):

maximum electric field



### **Potential**

Potential variation across the junction:

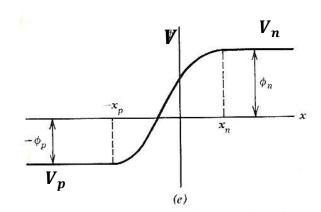
$$V(x) = V_n - \frac{qN_d}{2\epsilon_s} (x_n - x)^2 \qquad 0 < x < x_{n0}$$

$$V(x) = V_p - \frac{qN_a}{2\epsilon_s} (x + x_p)^2 \qquad -x_{p0} < x < 0$$

where 
$$V_n = \frac{kT}{q} ln \frac{N_d}{n_i}$$
 
$$V_p = -\frac{kT}{q} ln \frac{N_a}{n_i}$$

Built-in variation:

$$V_0 = V_n - V_p = \frac{kT}{q} \ln \frac{N_d N_a}{n_i}$$



### The contact potential

The contact potential can also be obtained by

$$\mathcal{E}(x) = -\frac{dV(x)}{dx} \text{ or } -V_0 = \int_{-x_{p0}}^{x_{n0}} \mathcal{E}(x) dx$$

$$\boldsymbol{V_0} = -\frac{1}{2} \mathcal{E}_0 W = \frac{1}{2} \frac{q}{\epsilon} N_d x_{n0} W$$

Since 
$$x_{p0}N_a = x_{n0}N_d$$
 and  $x_{p0} + x_{n0} = W$ 

### Depletion width

The depletion width is:

$$W = \left[\frac{2\epsilon V_0}{q} \left(\frac{N_a + N_d}{N_a N_d}\right)\right]^{1/2} = \left[\frac{2\epsilon V_0}{q} \left(\frac{1}{N_d} + \frac{1}{N_a}\right)\right]^{1/2}$$

where 
$$V_0 = \frac{kT}{q} ln \left( \frac{N_a N_d}{n_i^2} \right)$$

• The transition width  $W \propto \sqrt{V_0}$ . Applying voltage to increase or decrease the potential  $V_0$ , can modulate the depletion width of the junction.

## Penetration depth

 The penetration of the transition region into the n and p region:

$$x_{p0} = W \frac{N_d}{N_a + N_d}$$

$$x_{n0} = W \frac{N_d}{N_a + N_d}$$

 The transition region extends farther into the side with lighter doping.

### One-side junction

• If  $N_a \gg N_d$ , as in a p<sup>+</sup>n junction:

$$W = \sqrt{\frac{2\epsilon V_0}{qN_d}}$$

$$x_{p0} = W \frac{N_d}{N_a + N_d} \approx 0$$

- What abut a n<sup>+</sup>p junction?
- Generally:

$$W = \sqrt{\frac{2\epsilon V_0}{qN}}$$
 Where  $\frac{1}{N} = \frac{1}{N_d} + \frac{1}{N_a} \approx \frac{1}{lighter\ dopant\ density}$ 

• Ex: An abrupt silicon p-n junction has p-side  $N_A = 10^{18}$  cm<sup>-3</sup>, and n-side  $N_D = 5 \times 10^{15}$  cm<sup>-3</sup>. A) Calculate Fermi levels and built-in potential at equilibrium, B) How wide is the depletion region C) What is the maximum electric field.

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$$E_{ip} - E_F = rac{kT}{q} ln \left(rac{P_p}{n_i}
ight) = 0.467 eV$$
 $E_{fp} - E_{in} = rac{kT}{q} ln \left(rac{n_n}{n_i}
ight) = 0.329 eV$ 
 $E_{ip} - E_{ip} - E_{in} = 0.796 eV$ 
 $E_{vp} - \frac{1}{0.329 eV} = \frac{E_{fp}}{E_{vp}}$ 
or  $V_0 = rac{kT}{q} ln \left(rac{N_a N_d}{n_i^2}
ight) = 0.796 eV$ 

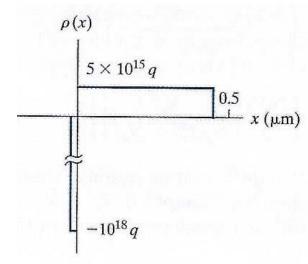
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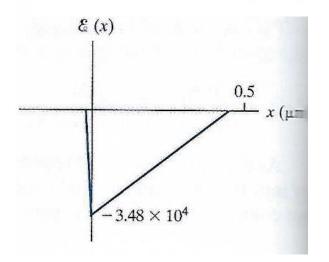
$$W = \left[\frac{2\epsilon V_0}{q} \left(\frac{1}{N_d} + \frac{1}{N_a}\right)\right]^{1/2} = 0.457 \mu m$$

$$x_{p0} = W \frac{N_d}{N_a + N_d} = 2.27 \times 10^{-3} \mu m$$

$$x_{n0} = W \frac{N_a}{N_a + N_d} = 0.455 \mu \text{m}$$

$$\mathcal{E}_0 = -\frac{q}{\epsilon} N_d x_{n0} = -3.48 \times 10^4 V/cm$$





## Arbitrarily doped semiconductor

Define  $\phi = E_F - E_i$ , the Poisson equation can be written as:

Space charge density

$$\frac{d^2\phi}{dx^2} = -\frac{d\mathcal{E}(x)}{dx} = -\frac{\rho}{\epsilon} = -\frac{q}{\epsilon}(p - n + N_d - N_a)$$

permittivity of the medium

The carrier concentration: 
$$n = n_i e^{(\frac{q\phi}{kT})}$$
  $p = n_i e^{(-\frac{q\phi}{kT})}$ 

$$\sinh(x) = (e^x - e^{-x})/2$$

### Two special cases

- Dopant concentration varies gradually with position,
  - Example: diffused n type region
- Abrupt special variations of dopant concentration
  - PN junction

## Case I: Gradual-variation, Quasi-neutrality

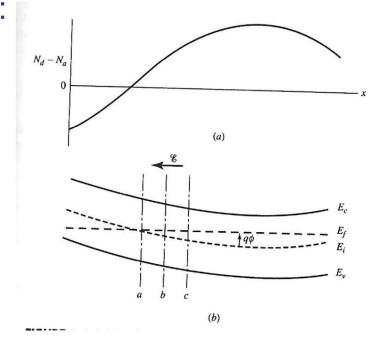
• Majority carrier distribution does not differ much from the donor (or acceptor) distribution, so that the semiconductor region is nearly neutral or quasi-neutral.  $n \approx N_d$ , or  $p \approx N_a$ .

This quasi-neutrality approximation is more valid for

slowly varying dopant densities. Then:

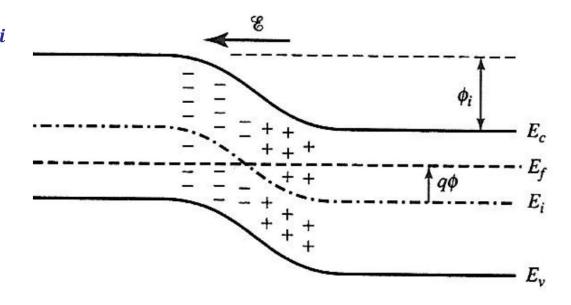
$$\varepsilon = \frac{kT}{q} \frac{1}{N_a} \frac{dN_a}{dx}$$

$$\varepsilon = -\frac{kT}{q} \frac{1}{N_d} \frac{dN_d}{dx}$$



## Case II: steep gradient

- In steep gradient, such as pn junction, the transition region is treated as if it were depleted of mobile carriers, i.e depletion approximation.
- The approximation is valid, because  $\phi = E_F E_i$  is small in the transition region. Since carrier concentration decrease rapidly as  $\phi$  becomes small, and are, consequently, much less in the transition region than in the neutral regions.



## Case II: steep gradient, depletion approximation

The Poisson equation can be simplified to:

$$\frac{d\mathcal{E}(x)}{dx} = \frac{q}{\epsilon} (N_d - N_a)$$

- For example:
  - Step junction (abrupt junction)
  - Linearly graded junction

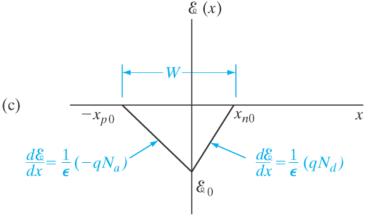
## Step junction: electric field and potential

### The electric field:

$$\mathcal{E}(x) = -\frac{qN_d}{\epsilon}(x_{n0} - x) \quad 0 < x < x_{n0}$$

$$\frac{d\mathcal{E}}{dx} = \frac{1}{\epsilon}(-qN_a)$$

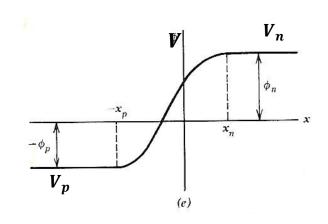
$$\mathcal{E}(x) = -\frac{qN_a}{\epsilon}(x_{p0} + x) \quad -x_{p0} < x < 0$$



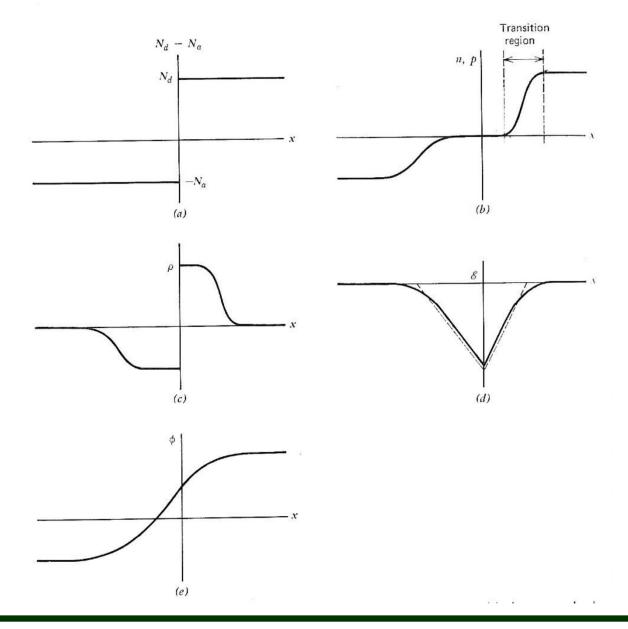
### The potential:

$$V(x) = V_n - \frac{qN_d}{2\epsilon_s} (x_n - x)^2 \qquad 0 < x < x_{n0}$$

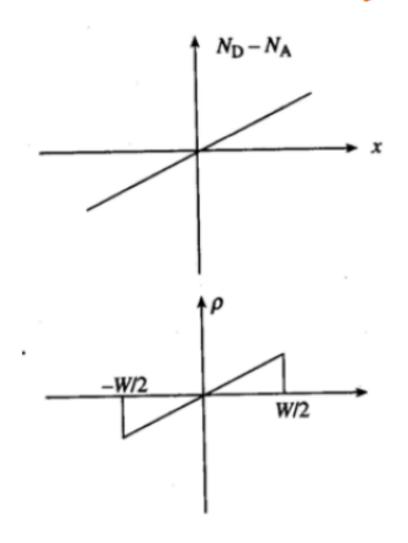
$$V(x) = V_p - \frac{qN_a}{2\epsilon_s} (x + x_p)^2 \qquad -x_{p0} < x < 0$$

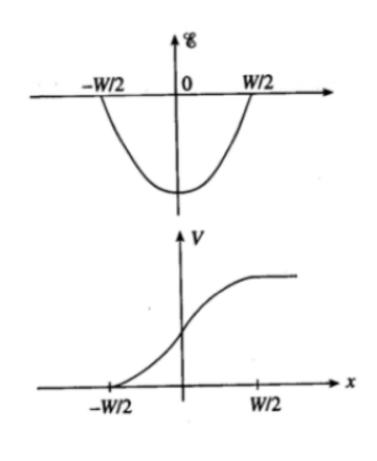


### Step junction considering a gradual transition



# Linearly Graded Junction





## Linear graded junction

- The dopant concentration:  $N_d N_a = \alpha x$
- The field varies quadratically and the potential varies as the third power of position in the space charge region

